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17. The method according to claim 14, further comprising:  
heat-treating the semiconductor layer while maintaining the  
temperature of the substrate in a range of 50 to 150°C after the  
semiconductor layer is formed by depositing the organic semiconductor.

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18. The method according to claim 14, further comprising:  
forming an electrode by depositing an electrode material on the  
semiconductor layer while maintaining the temperature of the substrate at  
45°C or less after the semiconductor layer is formed by depositing the organic  
semiconductor.

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19. An active matrix display comprising:  
a plurality of the organic thin film transistors according to claim 1 as  
switching elements for pixels.

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20. A radio recognition tag comprising:  
an integrated circuit portion,  
wherein the integrated circuit portion comprises the organic thin film  
transistor according to claim 1.

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